Coulomb blockade and electron interaction effects in strongly coupled metallic quantum dots

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2D

0D



g~1, ZBA



Coulomb Gap: How a Metal Film Becomes an Insulator

V. Yu. Butko,* J. F. DiTusa, and P. W. Adams Department of Physics and Astronomy; Louisiana State University; Baton Ronge, Louisiana 70806 (Received 10 September 1999)









Nanoparticle manipulation



Controlling the dot-lead coupling (electro-deposition)









PHYSICAL REVIEW B

Strong electron tunneling through mesoscopic metallic grains

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$$I(V) = G_{as}V - I_0(T, V) - \tilde{G}e^{-F(T,V)}V\cos 2\pi N$$

$$\frac{G(V)}{G_{as}} = 1 - \frac{1}{g_D} \left(\ln \left[1 + \frac{\hbar^2}{(2\pi t_c \epsilon)^2} \right] - \frac{2}{1 + (2\pi t_c \epsilon/\hbar)^2} \right) \\ + \exp \left[-\frac{g_D}{2} - \frac{2\pi^2}{\tilde{E_C}} \left(T + \frac{R_D}{R_S} V_{SD} \right) \right] \cos \left(\frac{2\pi V_{SD}}{E_C} + \phi \right)$$

Bitton, Gutman Berkovits and Frydman, arXiv:1007.4300











4.2K

77K



$$\frac{G(V)}{G_{as}} = 1 - \frac{1}{g_D} \left(\ln \left[1 + \frac{\hbar^2}{(2\pi t_c \epsilon)^2} \right] - \frac{2}{1 + (2\pi t_c \epsilon/\hbar)^2} \right) + \exp \left[-\frac{g_D}{2} - \frac{2\pi^2}{\tilde{E}_C} \left(T + \frac{R_D}{R_S} V_{SD} \right) \right] \cos \left(\frac{2\pi V_{SD}}{E_C} + \phi \right) (5)$$

 $\epsilon = (V^2 + \tilde{T}^2)^{1/2}$













\mathbf{V}_{SD} dependence



Vg







Single trajectory?





Summary



- Coupling controlled quantum dots with strong coupling asymmetry have been produced.
- The I-V curves show an combination of ZBA and coulomb blockade effects
- For strong coupling two gate-voltage periods are observed: one (fast) dominant at low source-drain voltage and the other (slow) at high voltage.
- The gate voltage curves seam to combine coulomb blockade effects and an additional process which is very sensitive to the energy.